L Number		Search Text	DB	Time stamp
1	434086		USPAT;	2004/01/09 18:16
		photo-sensitive (sensitive near (radiation	US-PGPUB;	
1		energy photo light))	EPO; JPO;	
2	0	(photoresist photo-resist photosensitive	DERWENT	
	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	photo-sensitive (sensitive near (radiation	USPAT; US-PGPUB;	2004/01/09 18:17
	ĺ	energy photo light))) same cavity same	EPO; JPO;	
ĺ		(expos\$3 irradiat\$5) same develop\$5 same	DERWENT	
		laminat\$5 same membrane		
4	151747	1 (management) model (layer film	USPAT;	2004/01/09 18:27
		coating)	US-PGPUB;	, , , , , , , , , , , , , , , , , , , ,
			EPO; JPO;	
5	13	(photoresist photo-resist photosensitive	DERWENT	
		photo-sensitive (sensitive near (radiation	USPAT; US-PGPUB;	2004/01/09 18:21
		energy photo light))) same (cavity channel	EPO; JPO;	
		microchannel micro-channel well microwell	DERWENT	
		micro-well chamber) same laminat\$5 same	DELWENT	
	105	membrane		
6	4909745		USPAT;	2004/01/09 18:22
		well microwell micro-well chamber)	US-PGPUB;	
			EPO; JPO;	
7	7959	(laminat\$5 cover\$3) with ((cover membrane)	DERWENT	
	,,,,,,	near2 (layer film coating)) with ((cover membrane)	USPAT;	2004/01/09 18:27
		channel microchannel micro-channel well	US-PGPUB; EPO; JPO;	
		microwell micro-well chamber))	DERWENT	
8	345	(photoresist photo-resist photosensitive	USPAT;	2004/01/09 18:24
		photo-sensitive (sensitive near (radiation	US-PGPUB;	
		energy photo light))) same ((laminat\$5	EPO; JPO;	
		cover\$3) with ((cover membrane) near2	DERWENT	1
		(layer film coating)) with ((cavity channel microchannel micro-channel well		
		microwell micro-well chamber))		
9	35	((photoresist photo-resist photosensitive	USPAT;	2004/01/00 10-04
		photo-sensitive (sensitive near (radiation	US-PGPUB;	2004/01/09 18:24
		energy photo light))) same ((laminat\$5	EPO; JPO;	
		cover\$3) with ((cover membrane) near2	DERWENT	
	Ì	(layer film coating)) with ((cavity		
		channel microchannel micro-channel well		
		microwell micro-well chamber)))) and (430/\$.ccls. 264/\$.ccls. 204/\$.ccls.		
		205/\$.ccls.)		
10	4826		USPAT;	2004/01/09 18:28
		((cavity channel microchannel	US-PGPUB;	2004/01/09 18:28
		micro-channel well microwell micro-well	EPO; JPO;	
11	1010	chamber))	DERWENT	
11	1810	(microfluid\$3 micro-fluid\$3 micro adj	USPAT;	2004/01/09 18:28
		fluid\$3) adj device	US-PGPUB;	
			EPO; JPO;	
12	46	((laminat\$5 cover\$3) with membrane with	DERWENT	2004/01/02 12 22
		((cavity channel microchannel	USPAT; US-PGPUB;	2004/01/09 18:30
]	micro-channel well microwell micro-well	EPO; JPO;	
	j	chamber))) and ((microfluid\$3	DERWENT	
		micro-fluid\$3 micro adj fluid\$3) adj		
1 5		device)		
15	21	(photoresist photo-resist photosensitive	USPAT;	2004/01/09 18:33
		photo-sensitive (sensitive near (radiation	US-PGPUB;	
		energy photo light))) same ((laminat\$5 cover\$3) with membrane with ((cavity	EPO; JPO;	
		channel microchannel micro-channel well	DERWENT	
		microwell micro-well chamber)))		
16	9468	(photoresist photo-resist photosensitive	USPAT;	2004/01/09 18:33
		photo-sensitive (sensitive near (radiation	US-PGPUB;	
		energy photo light))) near first!	EPO; JPO;	
	L		DERWENT	

17	8493	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!	USPAT; US-PGPUB;	2004/01/09	18:33
19	35491	photomask photo-mask photo adj mask	EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/01/09	18:34
22	30876	(electrode gate opaque shield\$3) near2 mask	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/01/09	18:36
23	10	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09	18:37
24	270		USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09	18:37
25	59	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)) same ((cavity channel micro-channel micro-channel well micro-well	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09	18:41
26	699	<pre>chamber)) ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09	18:41
27	741	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) with ((cavity channel microchannel micro-channel well micro-well chamber))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 1	18:41
28	18764	(electrochemical electro-chemical electro adj chemical) adj cell	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 1	18:41
29		photo-sensitive (sensitive near (radiation	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 1	8:42

				
31	37	(((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) adj cell)) and ((photoresist photo-resist photosensitive photo-sensitive (sensitive	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:45
		<pre>near (radiation energy photo light))) near first!) and ((photoresist photo-resist photosensitive photo-sensitive (sensitive</pre>		, ,
	į	<pre>near (radiation energy photo light))) near second!) and ((cavity channel micro-channel micro-channel well microwell micro-well chamber))</pre>		
32	86	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 18:45
33	126	<pre>(photomask photo-mask photo adj mask) ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)</pre>	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:46
34	0	(((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) with (((photoresist photo-resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:46
		photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) with (single near4 (expos\$3 irradiat\$5))		
35		(((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:48
36	0	second!) near4 ((electrode gate opaque shield\$3) near2 mask)) same (single near4 (expos\$3 irradiat\$5)) (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation	USPAT; US-PGPUB;	2004/01/09 18:47
		energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) same (one near4	EPO; JPO; DERWENT	
37	0	<pre>(expos\$3 irradiat\$5)) (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:47
38 1	10	second!) near4 ((electrode gate opaque shield\$3) near2 mask)) ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) same (photomask photo-mask photo adj mask) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) same	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:47
		((electrode gate opaque shield\$3) near2 mask)		

39	124196	(single one) near4 (expos\$3 irradiat\$5)	USPAT; US-PGPUB;	2004/01/09	18:49
			EPO; JPO;		
40	12	(photomask photo-mask photo adj mask) same	DERWENT	2004/04/04	
10	12	((electrode gate opaque shield\$3) near2	USPAT; US-PGPUB;	2004/01/09	18:53
		mask same ((single one)near4 (expos\$3	EPO; JPO;		
		irradiat\$5))	DERWENT		
41	40		USPAT;	2004/01/09	18:51
		cover\$3 with ((electrode gate opaque	US-PGPUB;		
		shield\$3) near2 mask)	EPO; JPO;		
42	710	(hack aids besteaids best aids aids)	DERWENT		
42	1 /10	(back-side backside back adj side) adj (expos\$3 irradiat\$5)	USPAT;	2004/01/09	18:52
		(enposys illadiatys)	US-PGPUB; EPO; JPO;		
		·	DERWENT		
43	734	(photomask photo-mask photo adj mask) same	USPAT;	2004/01/09	18:53
		((electrode gate opaque shield\$3) near2	US-PGPUB;	3001,01,05	10.55
		mask)	EPO; JPO;		
	_		DERWENT		
44	5	((photomask photo-mask photo adj mask)	USPAT;	2004/01/09	18:54
1		same ((electrode gate opaque shield\$3) near2 mask)) same ((back-side backside	US-PGPUB;		i
		back adj side) adj (expos\$3 irradiat\$5))	EPO; JPO; DERWENT		
46	1		USPAT;	2004/01/09	18.54
	İ	(expos\$3 irradiat\$5)) and 430/395.ccls.	US-PGPUB;	2004/01/03	10.54
			EPO; JPO;		
Ì			DERWENT		
_	60		USPAT;	2004/01/09	15:33
		MADOU-MARC-Jin. MADOU-MARK-Jin.	US-PGPUB;		ļ
	-	MADOU-M~Jin.	EPO; JPO;		
_	711108	resist photoresist photo-resist	DERWENT USPAT;	2004/01/09	17.54
		photosensitive photo-sensitive (sensitive	US-PGPUB;	2004/01/09	17:54
		near (photo light energy radiation))	EPO; JPO;		
			DERWENT		
-	11	(====	USPAT;	2004/01/09	15:45
		MADOU-MARC-Jin. MADOU-MARK-Jin.	US-PGPUB;		
		MADOU-M-Jin.) and (resist photoresist photo-resist photosensitive	EPO; JPO; DERWENT		
		photo-sensitive (sensitive near (photo	DERWENT		
	1	light energy radiation)))			
_	1810	(microfluid\$3 micro-fluid\$3 micro adj	USPAT;	2004/01/09	18:28
		fluid\$3) adj device	US-PGPUB;		
			EPO; JPO;		
_	4	(("4874500") or ("4900405")).PN.	DERWENT	0004/05/55	
	4	((40/4500) Of (4500405")), PN.	USPAT; US-PGPUB;	2004/01/09	15:46
			EPO; JPO;		
			DERWENT		İ
_	421	(resist photoresist photo-resist	USPAT;	2004/01/09	15:48
		photosensitive photo-sensitive (sensitive	US-PGPUB;		
		near (photo light energy radiation))) and	EPO; JPO;		
		((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device)	DERWENT		-
_	34233	(resist photoresist photo-resist	USPAT;	2004/01/09	15.40
		photosensitive photo-sensitive (sensitive	US-PGPUB;	2004/01/09	T7:48
		near (photo light energy radiation))) with	EPO; JPO;		İ
		negative	DERWENT		
_	75	((microfluid\$3 micro-fluid\$3 micro adj	USPAT;	2004/01/09	15:49
]	fluid\$3) adj device) and ((resist	US-PGPUB;		
		photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo	EPO; JPO;		ŀ
		light energy radiation))) with negative)	DERWENT		
-	96841	electrochemical electro-chemical electro	USPAT;	2004/01/09	15.52
]	adj chemical	US-PGPUB;	2001/01/09	10.02
			EPO; JPO;		ľ
	<u> </u>		DERWENT	_	_

-	0	(((resist photoresist photo-resist	USPAT;	2004/01/09 16:07
		photosensitive photo-sensitive (sensitive	US-PGPUB;	
ļ		near (photo light energy radiation))) with negative) same (cavity chamber)) same	EPO; JPO; DERWENT	
		((laminat\$5) with membrane)	DERWENT	
_	1153	liga!	USPAT;	2004/01/09 15:54
			US-PGPUB;	
			EPO; JPO; DERWENT	
	105		USPAT;	2004/01/09 15:59
		fluid\$3) adj device) and liga!	US-PGPUB;	2001/01/05 15:55
			EPO; JPO;	
_	68	liga! and 430/\$.ccls.	DERWENT USPAT;	2004/01/09 16:09
		1292. 41.4 18074.0019.	US-PGPUB;	2004/01/09 16:09
			EPO; JPO;	
	4964576	ghannal mi anashanashanashanashanashanashanashanas	DERWENT	
	4904376	channel microchannel micro-channel cavity chamber void well	USPAT;	2004/01/09 16:28
		oranger vota well	US-PGPUB; EPO; JPO;	
			DERWENT	
~	59543		USPAT;	2004/01/09 16:33
		photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with	US-PGPUB;	
		(channel microchannel micro-channel cavity	EPO; JPO; DERWENT	
		chamber void well)	DERWENT	
_	21		USPAT;	2004/01/09 16:33
		photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with	US-PGPUB;	
		(channel microchannel micro-channel cavity	EPO; JPO; DERWENT	
		chamber void well)) with cover\$3 with	DEKWENT	
	000	membrane		
_	202	(\= = = = 0 Pilo 00% 00 EDC Pilo CO ECO EDC	USPAT;	2004/01/09 16:35
		photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with	US-PGPUB; EPO; JPO;	
		(channel microchannel micro-channel cavity	DERWENT	
İ		chamber void well)) and ((microfluid\$3		
		micro-fluid\$3 micro adj fluid\$3) adj device)		
_	5499		USPAT;	2004/01/09 16:34
		photosensitive photo-sensitive (sensitive	US-PGPUB;	2004/01/09 16:34
		near (photo light energy radiation))) with	EPO; JPO;	
		(channel microchannel micro-channel cavity chamber void well) with (cover\$3 membrane	DERWENT	
		laminat\$5)		
-	36	((resist photoresist photo-resist	USPAT;	2004/01/09 16:42
		photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation))) with (channel microchannel micro-channel cavity)	EPO; JPO;	
		chamber void well) with (cover\$3 membrane	DERWENT	
		laminat\$5)) and ((microfluid\$3		
		micro-fluid\$3 micro adj fluid\$3) adj		
_	309	device) ((microfluid\$3 micro-fluid\$3 micro adj	Haby m	2004/01/02 15 15
		fluid\$3) adj device) with (method process	USPAT; US-PGPUB;	2004/01/09 16:45
		step) with (form\$3 formation manufactur\$3	EPO; JPO;	
_		produc\$5)	DERWENT	
-	1	(((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) with (method process	USPAT;	2004/01/09 16:44
İ		step) with (form\$3 formation manufactur\$3	US-PGPUB; EPO; JPO;	
	,	produc\$5)) same ((resist photoresist	DERWENT	
1		photo-resist photosensitive		
		photo-sensitive (sensitive near (photo light energy radiation))) with negative)		
_	15	(((microfluid\$3 micro-fluid\$3 micro adj	USPAT;	2004/01/09 16:47
[fluid\$3) adj device) with (method process	US-PGPUB;	2004/01/09 16:47
		step) with (form\$3 formation manufactur\$3	EPO; JPO;	
		<pre>produc\$5)) same (resist photoresist photo-resist photosensitive</pre>	DERWENT	
		photo-resist photosensitive photo-sensitive (sensitive near (photo		
		light energy radiation)))		

### Second Greate thetoresist photo-resist DEFAT: D					
processative photo-sensitive (sensitive mear (photo light energy radiation)) same membrane (channel microchannel photosensitive (sensitive near (photo light energy radiation))) same membrane same (channel microchannel microchannel microchannel microchannel microchannel microchannel cavity chamber void well) 25540 (resist photoresist photo-resist photosensitive photosensitive (sensitive near (photo light energy radiation))) 20915 (resist photoresist photo-resist photosensitive photosensitive photosensitive (sensitive near (photo light energy radiation))) 1310 (back-side back adj side backside) near2 (expos\$3 irradiat\$5) 4 ((resist photoresist photo-resist photosensitive photosensitive photosensitive photosensitive photosensitive (sensitive near (photo light energy radiation))) 1310 (increase photosensitive (sensitive near (photo light energy radiation))) 1310 (increase photosensitive (sensitive near (photo light energy radiation))) 1311 (increase photosensitive (sensitive photosensitive (sensitive near) (photo light energy radiation))) 1311 (increase photosensitive (sensitive near) (photo light energy radiation))) 1312 (increase photosensitive near (photo light energy radiation))) 1313 (increase photosensitive near) (photo light energy radiation)) 1314 (increase photosensitive near (photo light energy radiation))) 1315 (increase photosensitive near (photo light energy radiation)) in ear (increase photosensitive near) (photosensitive photosensitive near) (photosensitive near)	-	4966878	(resist photoresist photo-resist	USPAT;	2004/01/09 16:53
membrane (channel microchannel into-o-channel avaity chamber void well) (resist photoresist photo-resist photosensitive) near (photo light energy radiation)) same membrane same (channel microchannel micro-channel cavity chamber void well) (resist photosensitive) near (photo light energy radiation)) same micro-channel cavity chamber void well) (resist photosensitive photo-sensitive (sensitive photosensitive) near (photo light energy radiation)) same micro-channel micro-chann	•	ļ	photosensitive photo-sensitive (sensitive		
micro-channel cavity chamber void well) 1160 resist photoresists photo-resist photo-resist photo-sensitive near (photo light energy radiation)) same membrane same (channel micro-channel cavity chamber void well) (fresist photo-sensitive (sensitive rest (photo light energy radiation)) Same membrane same (channel micro-channel micro-c			near (photo light energy radiation))) same	EPO; JPO;	<u> </u>
The continue of the continue			membrane (channel microchannel	DERWENT	
photosensitive photo-sensitive (sensitive near (photo light energy radiation)) same membrane same (channel microchannel micro-channel cavity chamber void well) ((resist photoresist photo-resist photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive (sensitive near (photo light energy radiation))) same photosensitive photosensitive (sensitive near (photo light energy radiation))) 20915 (resist photoresist photo-resist photosensitive photosensitive (sensitive near (photo light energy radiation))) 210916 (resist photoresist photo-resist photosensitive photosensitive (sensitive near (photo light energy radiation))) 210917 (resist photoresist photo-resist photosensitive photosensitive (sensitive near (photo light energy radiation))) 210918 (resist photosensitive (sensitive near (photo light energy radiation))) 210919 (resist photosensitive (sensitive near (photo light energy radiation))) 210919 (resist photosensitive		1160	micro-channel cavity chamber void well)		
photosonsitive photo-sensitive (sensitive near (photo light energy radiation)) same membrane same (channel microchannel micro-channel cavity chamber void well) ((resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel micro-channel cavity chamber void well) and 430/\$.cic. 25540 (resist photoresist photo-resist photo-sensitive photo-sensitive (sensitive near (photo light energy radiation))) 20915 (resist photoresist photo-resist photo-sensitive photo-sensitive (sensitive near (photo light energy radiation))) 2150 (resist photoresist photo-resist photo-resist photo-resist photo-resist photo-sensitive (sensitive near (photo light energy radiation))) 227 (resist photoresist photo-resist pho	-	1100	(resist photoresist photo-resist	USPAT;	2004/01/09 16:55
membrane same (channel microchannel micro-channel cavity chanber void well) ((resist photoresist photo-resist photosonsitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel microchannel micro-channel cavity chamber void well) ad 430/S.cols. (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first! (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second! (back-side back adj side backside) near2 (irst) same (resist photoresist photo-resist photosensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photosensitive photo-sensitive photosensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) near2 first! 19879 19879 19879 19879 19879 2004/01/09 17:10 USPAT; U			photosensitive photo-sensitive (sensitive	US-PGPUB;	
membrane same (channel microchannel micro-channel cavity chanber void well) ((resist photoresist photo-resist photosonsitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel microchannel micro-channel cavity chamber void well) ad 430/S.cols. (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first! (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second! (back-side back adj side backside) near2 (irst) same (resist photoresist photo-resist photosensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photosensitive photo-sensitive photosensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive photo-sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 first!) near2 first! 19879 19879 19879 19879 19879 2004/01/09 17:10 USPAT; U	Ì		near (photo light energy radiation))) same	EPO; JPO;	
Comparison of the process of the p			membrane same (channel microchannel		
Comparison of the process of the p			micro-channel cavity chamber void well)		
photosensitive photo-sensitive (sensitive near (photo light energy radiation)) same membrane same (channel micro-channel micro-channel micro-channel cavity chamber void well)) and 430/\$.ccls. 25540 (resist photoresist photo-resist photosensitive photo-sensitive (sensitive macr (photo light energy radiation)) near2 first! 20915 (resist photoresist photo-resist photosensitive photosensitive photo-sensitive (sensitive near (photo light energy radiation)) near2 second! ((resist photoresist photo-resist photosensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same (resist photoresist photo-resist photo-resist photo-resist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos33 irradiat55)) same electrode light energy radiation))) near2 first!) same ((resist photoresist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos33 irradiat55)) same electrode of chemical photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos33 irradiat55)) same electrode of chemical photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same (float-side back adj side backside) near2 (expos33 irradiat55) 19879 (electrochemical electro-chemical electro-chemical electro-chemical electro-chemical) photomask photo-mask photo adj mask 2004/01/09 17:15 2004/01/09 17:15 USPAT: US-PGUB: EPO: JPO: DERWENT USPAT: US-PGUB: EPO: JPO: DERWENT USPAT: US-PGUB: EPO: JPO: DERWENT USPAT: U	_	86	((resist photoresist photo-resist	USPAT:	2004/01/09 17:08
membrane same (channel microchannel micro-channel micro-channel cavity chamber void well)) and 430/8.cds. 25540 (resist photoresist photo-resist photosensitive (sensitive near (photo light energy radiation))) near2 first! 20915 (resist photoresist photo-resist photosensitive (sensitive near (photo light energy radiation))) near2 second! 31500 (back-side back adj side backside) near2 (expos\$3 irradiat\$5) 4 ((resist photoresist photo-resist photosensitive photosensitive (sensitive photosensitive			photosensitive photo-sensitive (sensitive		2001,01,00 11.00
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photo-sensitive (sensitive near (photo light energy radiation)) near2 second!) same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5)) (electrochemical electro-chemical electro adj chemical) near cell 21676 ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro-chemical electro-chemical electro-chemical electro-adj chemical) near cell) 35491 photomask photo-mask photo adj mask 79461 (membrane cover) near (layer film) Photomask photo-sensitive near (photo light of photos adj second!) USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO;			photo-resist photosensitivo	DEKWENT	
light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5)) (electrochemical electro-chemical electro adj chemical) near cell 21676 ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell) photomask photo-mask photo adj mask 79461 (membrane cover) near (layer film) light energy radiation))) near2 second!) USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;			photo-sensitive (sensitive near /phot-		
same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5)) (electrochemical electro-chemical electro adj chemical) near cell 21676 ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell) photomask photo-mask photo adj mask 79461 (membrane cover) near (layer film) Same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5)) USPAT; USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;		[light energy radiation \\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\		
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adj chemical) near cell 21676 ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro adj chemical) near cell) near cell) photomask photo-mask photo adj mask 79461 (membrane cover) near (layer film) US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	~	19879	(electrochemical electro-chomical al	HODAG	0004/04/55
21676 ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell) photomask photo-mask photo adj mask 79461 (membrane cover) near (layer film) EPO; JPO; DERWENT USPAT; 2004/01/09 17:48 US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT;			adi chemical) noar coll		2004/01/09 17:16
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21676 ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell) photomask photo-mask photo adj mask 79461 (membrane cover) near (layer film) USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO;					
fluid\$3) adj device) ((electrochemical electro-chemical electro-adj chemical) near cell) photomask photo-mask photo adj mask 79461 (membrane cover) near (layer film) US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO;	_	21676	((microfluid\$3 micro-fluid\$3 =====		
electro-chemical electro adj chemical) near cell) photomask photo-mask photo adj mask Topic description of the property of the photomask photo adj mask Topic description of the property of the photomask photo adj mask Topic description of the property of the photomask photo adj mask Topic description of the property of the photomask photo adj mask Topic description of the property of the photomask photo adj mask Topic description of the property of the photomask photo adj mask Topic description of the property of the photomask photo adj mask Topic description of the photomask photo adj mask Topic description of the photomask photomask photo adj mask Topic description of the photomask photomask photomask photomask photomask photomask photomask photomask Topic description of the photomask photomask photomask photomask photomask photomask Topic description of the photomask p		210,0	fluid\$3) adi dovice \ //21-1		2004/01/09 17:48
- 35491 near cell) photomask photo-mask photo adj mask DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;]	electro-chomical alactro-chemical		
79461 (membrane cover) near (layer film) 35491 photomask photo-mask photo adj mask USPAT; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO;			near cell		
T9461 (membrane cover) near (layer film) US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;					
- 79461 (membrane cover) near (layer film) EPO; JPO; DERWENT USPAT; 2004/01/09 17:20 US-PGPUB; EPO; JPO;		20431	photomask photo-mask photo adj mask		2004/01/09 17:19
Terminal (membrane cover) near (layer film) DERWENT USPAT; 2004/01/09 17:20 US-PGPUB; EPO; JPO;]			
79461 (membrane cover) near (layer film) USPAT; 2004/01/09 17:20 US-PGPUB; EPO; JPO;		i			
US-PGPUB; EPO; JPO;	_	70461	/	DERWENT	
EPO; JPO;		/9461	(memorane cover) near (layer film)	USPAT;	2004/01/09 17:20
					1
DERWENT				EPO; JPO;	ĺ
		<u> </u>		DERWENT	

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i -	0	I CCC TELEGIST TO THE CELL METOTO TELEGIST METOTO METOTO	USPAT;	2004/01/09 17:22
		fluid\$3) adj device) ((electrochemica)	US-PGPUB;	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1
ļ	Í	electro-chemical electro adj chemical)	EPO; JPO;	
		near cell)) and ((resist photoresist	DERWENT	
		photo-resist photosensitive		
		photo-sensitive (sensitive near (photo		
		light energy radiation))) same (photomask		
	į	photo-mask photo adj mask) same ((membrane		
		cover) near (layer film)) same (channel		
		microchannel micro-channel cavity chamber		
	ļ	void well))		
-	8		USPAT;	2004/01/09 17:24
		photosensitive photo-sensitive (sensitive	US-PGPUB;	2001/01/03 17.24
		near (photo light energy radiation))) same	EPO; JPO;	
		(photomask photo-mask photo add mask) same	DERWENT	
	ļ	((membrane cover) near (laver film)) same		
		(channel microchannel micro-channel cavity		
		chamber void well))		
-	29	T CLU ACT	USPAT;	2004/01/09 17:26
			US~PGPUB;	
		electro-chemical electro adj chemical)	EPO; JPO;	
	i	near cell)) and ((resist photoresist	DERWENT	1
		photo-resist photosensitive		
		photo-sensitive (sensitive near (photo		
		light energy radiation))) and (photomask		İ
		photo-mask photo adj mask) and ((membrane		
	i	cover) near (layer film)) and (channel		
		microchannel micro-channel cavity chamber		
		void well))		
-	28590	1 (USPAT;	2004/01/09 17:51
		photosensitive photo-sensitive (sensitive	US-PGPUB;	2001,01,03 1,.31
	İ	near (photo light energy radiation))) with	EPO; JPO;	!
		(develop\$5 etch\$4 form\$3) with (channe)	DERWENT	
		microchannel micro-channel cavity chamber		
		void well)		1
-	50	((resist photoresist photo-resist	USPAT;	2004/01/09 17:54
		photosensitive photo-sensitive (sensitive	US-PGPUB;	,,,,,,,,,
1		near (photo light energy radiation))) with	EPO; JPO;	
		(develop\$5 etch\$4 form\$3) with (channel	DERWENT	
		microchannel micro-channel cavity chamber		
		void well)) same (fluid near2		
	101000	communication)		
_	434086	photoresist photo-resist photosensitive	USPAT;	2004/01/09 17:54
		photo-sensitive (sensitive near (photo	US-PGPUB;	= 3 1 1 7 1 2 7 1 3 1
		light energy radiation))	EPO; JPO;	
	200000		DERWENT	
_	392389	(channel microchannel micro-channel cavity	USPAT;	2004/01/09 18:02
		chamber void well) near2 (two large\$1	US-PGPUB;	
]	small\$2 big\$4)	EPO; JPO;	İ
_			DERWENT	
_	29	((channel microchannel micro-channel	USPAT;	2004/01/09 18:03
	}	cavity chamber void well) near2 (two	US-PGPUB;	
		large\$1 small\$2 big\$4)) same ((resist	EPO; JPO;	
		photoresist photo-resist photosensitive	DERWENT	
		photo-sensitive (sensitive near (photo		İ
	ļ	light energy radiation))) near2 first!)		
	j	same ((resist photoresist photo-resist)		ļ
		photosensitive photo-sensitive (sensitive		
•	İ	near (photo light energy radiation)))		
	L	near2 second!)		